

## PATENT APPLICATION

R. Fuller

105193.01

Group Art Unit: 285

Examiner:

Docket No.:

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Hideki KOMATSUDA

Application No.: 09/697,639

Filed: October 27, 2000

EXPOSURE APPARATUS AND METHOD OF FABRICATING A MICRO DEVICE

USING THE EXPOSURE APPARATUS

**AMENDMENT** 

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

For:

Further to the Request For Continued Examination (RCE) filed on November 2002, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 16, 19, 22, 33 and 34 as follows:

16. (Amended) The exposure apparatus of claim 1, wherein the illumination optical system comprises:

a radiation source that outputs a radiation beam;

a reflective optical integrator that makes uniform an illumination distribution of radiation from the radiation beam; and

a radiation guiding optical system arranged in an optical path between the radiation source and the reflective optical integrator, and that guides the radiation beam from

the radiation source to the reflective optical integrator.

12/17/2002 SSESHE1 00000115 09697639

01 FC:1202 02 FC:1201

672.00 OP 🛩